SOFT PLASMA IGNITION IN PLASMA PROCESSING CHAMBERS

Abstract of the Disclosure

The specification discloses a power supply circuit (30) which reduces oscillations (26) generated upon ignition of a plasma within a processing chamber (14). A secondary power supply (32) pre-ignites the plasma by driving the cathode (12) to a process initiation voltage. Thereafter, a primary power supply (10) electrically drives the cathode (12) to generate plasma current and deposition on a wafer (16).

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